

PROGRAMME

Mercredi 4 novembre 2020 – après-midi	
14:00-14:15	Ouverture
14:15-14:30	New Spatial ALD/CVD approaches for Area-Selective Deposition and 3D Printing of functional materials , Chiara Crivello, <i>LMGP, Grenoble</i> ,
14:30-14:45	Analyses des interfaces InGaN-Al₂O₃ déposé par ALD pour la passivation des flancs de μLED bleues , Corentin Le Maout, <i>CEA, LETI, Grenoble</i>
14:45-15:00	Material engineering of ALD- deposited hetero-nano structures to improve the superconducting performances of RF cavities under intense RF fields , Yasmine Kalboussi, <i>CEA-IRFU, Saclay</i>
15:10-15:25	Humidity Resistant Gas Sensors Based on SnO₂ Nanowires Coated with a Porous Alucone Converted Nanomembrane by Molecular Layer Deposition , Syreina ALSAYEGH, <i>IEM, Montpellier</i>
15:25-15:40	Thermal and Plasma-assisted Atomic Layer Deposition of TiN and Pd for Hydrogen Separative Membranes , Clémence Badie, <i>CINAM, Marseille</i>
15:40-15:55	SnO₂ déposé par ALD pour des cellules solaires tandem pérovskite/silicium , Félix Gayot, <i>INES, Le Bourget du Lac</i>
16:05-16:20	Élaboration et caractérisations de couches minces d'oxyde d'hafnium : application à la ferroélectricité pour les mémoires , I. Bottala-Gambetta, <i>SIMaP, Grenoble</i>
16:20-16:35	Chemical passivation of ALD-ZnO by phosphonic acid derivatives , Olivier Fournier, <i>IPVF, Palaiseau</i>
16:35-16:50	An atomic-layer 3D printer , Maïssa Barr, <i>Friedrich-Alexander University of Erlangen-Nürnberg, Erlangen</i>

Jeudi 5 novembre 2020 – matin	
9:15-9:30	Palladium nanoparticles coated on titanium dioxide nanofibers by atomic layer deposition as effective photoelectrocatalyst for water treatment under visible light , Fida TANOS, <i>IEM Montpellier</i>
9:30-9:45	Croissance épitaxiale de matériaux piézoélectriques pour la réalisation des prochaines générations de filtres 5G , J. Patouillard, <i>SIMaP, Grenoble</i>
9:45-10:00	Structural and optical characterizations of TiO₂ thin films deposited on different substrates by ALD technique , Aline Jolivet, <i>CIMAP, Caen</i>
10:10-10:25	Optimization of a Topographic Selective Deposition (TSD) route by a super-cycle Atomic Layer Disposition (ALD) / Atomic Layer Etching (ALE) , Moustapha JAFFAL, <i>LTM, Grenoble</i>
10:25-10:40	Potential of amidinate gallium complexes as precursors for Atomic Layer Deposition , Paul-Alexis Pavard, <i>IPVF, Palaiseau</i>
10:40-10:55	Open-air ALD Printing of Functional Thin Films for Solar Cells , Abderrahime Sekkat, <i>LMGP, Grenoble</i>
11:05-11:20	Innovative transparent conductive electrode by atomic layer deposition for Si nanowire solar cells , Shan-Ting Zhang, <i>IPVF, Palaiseau</i>
11:20-11:35	In situ X-ray studies of Dichalcogenide Molecular Layer Deposition and thermal annealing , P. Abi Younes, <i>LMGP, Grenoble</i>
12:00	Remise du prix de l'oral